

	Hits	Search Text	DBs
1	116	((substrate or wafer or (silicon near12 \$2oxide) or platen or device) same (contact or line) same (opening or groov\$2 or hole or via or trench) same ((form\$4 or deposit\$4 or coat\$3 or film\$3) near22 (resist or photoresist) near24 (pattern\$4 or lithograph\$6) near16 (expos\$4 or illuminat\$4 or irradiat\$4)) same (CMP or planarize or (etch\$4 near12 flush\$4)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	21	((substrate or wafer or (silicon near12 \$2oxide) or platen or device) same (contact or line) same (opening or groov\$2 or hole or via or trench) same ((form\$4 or deposit\$4 or coat\$3 or film\$3) near22 (resist or photoresist or cur\$5) near24 (pattern\$4 or lithograph\$6 or expos\$4 or illuminat\$4 or irradiat\$4)) same (CMP or planariz\$4) same (aluminum or Al or metal\$4 or wiring or circuit\$4 or conductive)) and ((resist or photoresist) same (negative or positive) same (mask or photomask or reticle) same (opening or (transmit\$4 near6 portion) or (transparent near6 (area or portion))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
3	19	((substrate or wafer or (silicon near12 \$2oxide) or platen or device) same (contact or line or trace) same (opening or groov\$2 or hole or via or trench) same ((form\$4 or deposit\$4 or coat\$3 or film\$3) near22 (resist or photoresist or cur\$5) near24 (pattern\$4 or lithograph\$6 or expos\$4 or illuminat\$4 or irradiat\$4)) same (CMP or planariz\$4) same (aluminum or Al or metal\$4 or wiring or circuit\$4 or conductive)) and ((resist or photoresist) same (negative or positive)) and ((mask or photomask or reticle) near19 (opening or (transmit\$4 near6 (region or portion or area)) or (transparent near6 (area or portion))) near22 (contact or line or trace))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
4	2	((("6146968") or ("6100177"))).PN.	US-PGPUB; USPAT

	Hits	Search Text	DBs
5	3	((substrate or wafer or (silicon near12 \$2oxide) or platen or device or base) same (contact or line or trace) same (opening or groov\$2 or hole or via or trench) same ((form\$4 or deposit\$4 or coat\$3 or film\$3) near22 (resist or photoresist) near24 (planariz\$4 or CMP or polish\$4) near12 (open\$4 or hole or via or groove)) same (pattern\$4 or lithograph\$5)) and ((interlayer or insulating or capacitor) same (mask or photomask or reticle) same (light\$6shield\$5portion or opaque or (light near12 block\$4 near14 (portion or region or area))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	2	((substrate or wafer or (silicon near12 \$2oxide) or platen or device or base) same (contact or line or trace) same (opening or groov\$2 or hole or via or trench) same ((form\$4 or deposit\$4 or coat\$3 or film\$3) near22 (resist or photoresist) near24 (planariz\$4 or CMP or polish\$4) near12 (open\$4 or hole or via or groove)) same (pattern\$4 or lithograph\$5)) and ((mask or photomask or reticle) same (light\$6shield\$5portion or opaque or (light near12 block\$4 near14 (portion or region or area))) same (opening or hole or via or groove or trench) same (substrate or wafer or base or interlayer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
7	4	((substrate or wafer or (silicon near12 \$2oxide) or platen or device or base) same (conductive or metal\$3 or aluminum or Al or insulat\$4 or oxide or second) same (opening or groov\$2 or hole or via or trench) same ((form\$4 or deposit\$4 or coat\$3 or film\$3) near22 (resist or photoresist) near24 (planariz\$4 or CMP or polish\$4) near12 (open\$4 or hole or via or groove)) same (pattern\$4 or lithograph\$5or expos\$4 or irradiat\$4 or illuminat\$4)) and ((mask or photomask or reticle) same (light\$6shield\$5portion or opaque or (light near12 block\$4 near14 (portion or region or area))) same (opening or hole or via or groove or trench) same (substrate or wafer or base or interlayer)) and (contact or line or trace)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
8	2	((substrate or wafer or (silicon near12 \$2oxide) or platen or device or base) same (conductive or metal\$3 or aluminum or Al or insulat\$4 or oxide or second) same (opening or groov\$2 or hole or via or trench) same ((form\$4 or deposit\$4 or coat\$3 or film\$3) near22 (resist or photoresist) near24 (planariz\$4 or CMP or polish\$4) near12 (open\$4 or hole or via or groove)) same (pattern\$4 or lithograph\$5 or expos\$4 or irradiat\$4 or illuminat\$4) same develop\$5) and ((mask or photomask or reticle) same (light\$6shield\$5portion or opaque or (light near12 block\$4 near14 (portion or region or area)))) and (contact or line or trace)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
9	16	((substrate or wafer or (silicon near12 \$2oxide) or platen or device or base) same (opening or groov\$2 or hole or via or trench) same ((form\$4 or deposit\$4 or coat\$3 or film\$3 or fill\$3) near22 (resist or photoresist) near16 (expos\$4 or illuminat\$4 or irradiat\$4) near22 negative) same (CMP or planariz\$4 or etchback)) and ((contact near9 hole) or line or contact or trace) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	1	("5691215").PN.	US-PGPUB; USPAT

	Hits	Search Text	DBs
11	61	((substrate or wafer or (silicon near12 \$2oxide) or platen or device or base) same ((form\$4 or deposit\$4 or coat\$3 or film\$3) near22 (resist or photoresist) near24 (expos\$4 or illuminat\$4 or irradiat\$4) near26 negative) same ((mask or reticle or photomask) near12 (light\$6shield\$8 or opaque or light\$9block\$5 or opening or transparent or transmit\$6) near16 (size or small\$3 or area)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
12	16	((substrate or wafer or (silicon near12 \$2oxide) or platen or device or base) same ((form\$4 or deposit\$4 or coat\$3 or film\$3) near22 (resist or photoresist) near24 (expos\$4 or illuminat\$4 or irradiat\$4) near26 negative) same ((mask or reticle or photomask) near12 (light\$6shield\$8 or opaque or light\$9block\$5 or opening or transparent or transmit\$6) near16 (size or small\$3 )))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
13	37	((substrate or wafer or (silicon near12 \$2oxide) or platen or device or base) same ((form\$4 or deposit\$4 or coat\$3 or film\$3) near22 (resist or photoresist) near24 (expos\$4 or illuminat\$4 or irradiat\$4)) same ((mask or reticle or photomask) near12 (light\$6shield\$8 or opaque or light\$9block\$5 or opening or transparent or transmit\$6) near16 small\$3)) and ((resist or photoresist) near16 negative)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB